

Specification for the book of courses

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|--|---|---|--------------------------------|----------------------|
| Study program | | Electrical Engineering and Computer Science | | |
| Module | | Electron Devices and Microsystems | | |
| Type and level of studies | | Undergraduate Academic Studies | | |
| The name of the course | | Microsystem Technologies | | |
| Lecturer (for lectures) | | Paunović V. Vesna, Pešić M. Biljana | | |
| Lecturer/associate (for exercises) | | Marjanović B. Miloš, Paunović V. Vesna | | |
| Lecturer/associate (for OFE) | | Marjanović B. Miloš | | |
| Number of ECTS | 6 | Course status (obligatory/elective) | Obligatory | |
| Prerequisites | | | | |
| Course objectives | Learning basic knowledge of materials for microsystems, and the most important technological processes in various technologies for microsystems realization, as well as the assembly and microsystems integration. | | | |
| Course outcomes | Theoretical knowledge about the technologies for microsystems realization. Numerical solving of problems in the field of technological processes. Practical simulation of the semiconductor substrates production, oxidation, diffusion, ion implantation, lithography, etching, metallization | | | |
| Course outline | | | | |
| Theoretical teaching | Definitions and classification of microsystems. Materials for microsystems. Microelectronic technologies: films growth and deposition, doping, lithography, etching, Ion implantation, oxidation, diffusion. Bulk micromachining technology: technological processes, structures, applications. Surface micromachining technology: technological processes, structures, applications, LIGA technologies: technological processes, applications. Assembly and microsystems integration | | | |
| Practical teaching (exercises, OFE, study and research) | Practical exercises showing numerical problem solving in the technological processes. Exercises are performed on a computer using the simulator of technological processes. Preparation of semiconductor substrates, epitaxial growth, oxidation, diffusion, ion implantation, lithography, etching, metallization, CMOS technological array | | | |
| Textbooks/references | | | | |
| 1 | G.S.May, C.J. Spanos, Fundamentals of Semiconductor manufacturing and process control, John Wiley, 2006 | | | |
| 2 | G.Gerlach, W Dotzel, D.Muller, Introduction to Microsystem technology, John Wiley, 2008 | | | |
| 3 | V. Barzdenas, R. Navickas, Microtechnologies, a laboratory manual, Vilnius Technika, 2012 | | | |
| 4 | L. A. Francis, K. Iniewski, Novel Advances in Microsystems Technologies and Their Applications, CRC Press, 2017 | | | |
| 5 | V. Vardan, K. Vinoy and S. Gopalakrishnan, Smart Material Systems and MEMS, John Wiley, 2006 | | | |
| Number of classes of active education per week during semester/trimester/year | | | | |
| Lectures | Exercises | OFE | Study and research work | Other classes |
| 2 | 2 | 1 | 0 | 0 |
| Teaching methods | Lectures, practice work, consultations | | | |
| Grade (maximum number of points 100) | | | | |
| Pre-exam duties | Points | Final exam | Points | |
| Activity during lectures | 5 | Written exam | 25 | |
| Exercises | 20 | Oral exam | 25 | |
| Colloquia | 20 | | | |
| Projects | 5 | | | |